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* * * * * Welcome to STN International * * * * *

| | | | |
|------|----|--------|---|
| NEWS | 1 | | Web Page for STN Seminar Schedule - N. America |
| NEWS | 2 | DEC 01 | ChemPort single article sales feature unavailable |
| NEWS | 3 | JUN 01 | CAS REGISTRY Source of Registration (SR) searching enhanced on STN |
| NEWS | 4 | JUN 26 | NUTRACEUT and PHARMAML no longer updated |
| NEWS | 5 | JUN 29 | IMSCOPROFILE now reloaded monthly |
| NEWS | 6 | JUN 29 | EPFULL adds Simultaneous Left and Right Truncation (SLART) to AB, MCLM, and TI fields |
| NEWS | 7 | JUL 09 | PATDPAFULL adds Simultaneous Left and Right Truncation (SLART) to AB, CLM, MCLM, and TI fields |
| NEWS | 8 | JUL 14 | USGENE enhances coverage of patent sequence location (PSL) data |
| NEWS | 9 | JUL 27 | CA/CAplus enhanced with new citing references |
| NEWS | 10 | JUL 16 | GBFULL adds patent backfile data to 1855 |
| NEWS | 11 | JUL 21 | USGENE adds bibliographic and sequence information |
| NEWS | 12 | JUL 28 | EPFULL adds first-page images and applicant-cited references |
| NEWS | 13 | JUL 28 | INPADOCDB and INPAFAMDB add Russian legal status data |
| NEWS | 14 | AUG 08 | Improve STN by completing a survey and be entered to win a gift card |
| NEWS | 15 | AUG 10 | Time limit for inactive STN sessions doubles to 40 minutes |
| NEWS | 16 | AUG 17 | CAS REGISTRY, the Global Standard for Chemical Research, Approaches 50 Millionth Registration Milestone |
| NEWS | 17 | AUG 18 | COMPENDEX indexing changed for the Corporate Source (CS) field |

NEWS EXPRESS MAY 26 09 CURRENT WINDOWS VERSION IS V8.4,
AND CURRENT DISCOVER FILE IS DATED 06 APRIL 2009.

NEWS HOURS STN Operating Hours Plus Help Desk Availability
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* * * * *

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 *
 * See NEWS 14 for details or go directly to the survey at: *
 * <http://www.zoomerang.com/Survey/?p=WEB229H4S8Q5UL> *
 *

* * * * * STN Columbus * * * * *

FILE 'HOME' ENTERED AT 13:35:12 ON 18 AUG 2009

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|------------|---------|
| ENTRY | SESSION |
| 0.22 | 0.22 |

FULL ESTIMATED COST

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STRUCTURE FILE UPDATES: 17 AUG 2009 HIGHEST RN 1174495-28-3
 DICTIONARY FILE UPDATES: 17 AUG 2009 HIGHEST RN 1174495-28-3

New CAS Information Use Policies, enter HELP USAGETERMS for details.

TSCA INFORMATION NOW CURRENT THROUGH June 26, 2009.

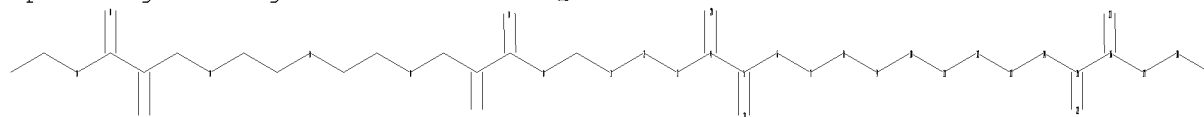
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<http://www.cas.org/support/stngen/stndoc/properties.html>

=>

Uploading C:\Program Files\STNEXP\Queries\10567430clm58.str



chain nodes :
 1 2 3 4 5 6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 23
 chain bonds :
 1-2 2-3 3-4 4-5 4-20 5-6 5-21 6-7 7-8 8-9 9-10 10-11 11-12 12-13
 13-14 14-15 15-16 15-22 16-17 16-23 17-18 18-19
 exact/norm bonds :
 2-3 3-4 4-20 6-7 7-8 9-10 10-11 12-13 13-14 16-17 16-23 17-18
 exact bonds :

1-2 4-5 5-6 5-21 8-9 11-12 14-15 15-16 15-22 18-19

Match level :

1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 9:CLASS
10:CLASS 11:CLASS 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS
18:CLASS 19:CLASS 20:CLASS 21:CLASS 22:CLASS 23:CLASS

L1 STRUCTURE UPLOADED

=> d l1

L1 HAS NO ANSWERS

L1 STR

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

Structure attributes must be viewed using STN Express query preparation.

=> s l1 sss sam

SAMPLE SEARCH INITIATED 13:36:07 FILE 'REGISTRY'

SAMPLE SCREEN SEARCH COMPLETED - 421 TO ITERATE

100.0% PROCESSED 421 ITERATIONS

0 ANSWERS

SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**

BATCH **COMPLETE**

PROJECTED ITERATIONS: 7189 TO 9651

PROJECTED ANSWERS: 0 TO 0

L2 0 SEA SSS SAM L1

=> s l1 sss full

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FULL SCREEN SEARCH COMPLETED - 7246 TO ITERATE

100.0% PROCESSED 7246 ITERATIONS

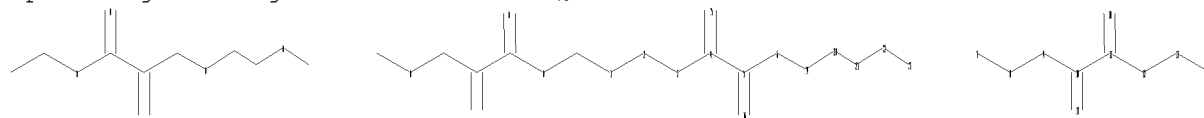
0 ANSWERS

SEARCH TIME: 00.00.01

L3 0 SEA SSS FUL L1

=>

Uploading C:\Program Files\STNEXP\Queries\10567430clm58b.str



chain nodes :

1 2 3 4 5 6 7 8 9 10 11 12 13 14 15 16 17 18 19 20 21 22 23

chain bonds :

1-2 2-3 3-4 4-5 4-15 5-6 5-16 6-19 7-8 8-9 9-10 10-11 10-17 11-12

11-18 12-13 13-14 19-20 20-21 21-22 22-23

exact/norm bonds :
2-3 3-4 4-15 6-19 7-8 8-9 11-12 11-18 12-13 19-20 21-22 22-23
exact bonds :
1-2 4-5 5-6 5-16 9-10 10-11 10-17 13-14 20-21

Match level :
1:CLASS 2:CLASS 3:CLASS 4:CLASS 5:CLASS 6:CLASS 7:CLASS 8:CLASS 9:CLASS
10:CLASS 11:CLASS 12:CLASS 13:CLASS 14:CLASS 15:CLASS 16:CLASS 17:CLASS
18:CLASS 19:CLASS 20:CLASS 21:CLASS 22:CLASS 23:CLASS

L4 STRUCTURE UPLOADED

=> d l4
L4 HAS NO ANSWERS
L4 STR

* STRUCTURE DIAGRAM TOO LARGE FOR DISPLAY - AVAILABLE VIA OFFLINE PRINT *

Structure attributes must be viewed using STN Express query preparation.

=> s l4 sss sam
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SAMPLE SCREEN SEARCH COMPLETED - 421 TO ITERATE

100.0% PROCESSED 421 ITERATIONS 0 ANSWERS
SEARCH TIME: 00.00.01

FULL FILE PROJECTIONS: ONLINE **COMPLETE**
BATCH **COMPLETE**
PROJECTED ITERATIONS: 7189 TO 9651
PROJECTED ANSWERS: 0 TO 0

L5 0 SEA SSS SAM L4

=> s l4 sss full
FULL SEARCH INITIATED 13:46:29 FILE 'REGISTRY'
FULL SCREEN SEARCH COMPLETED - 7246 TO ITERATE

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SEARCH TIME: 00.00.01

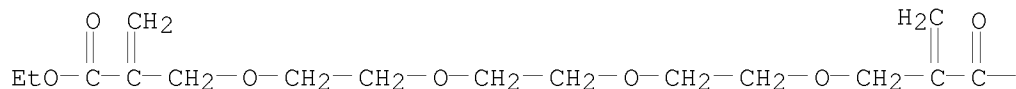
L6 4 SEA SSS FUL L4

=> d scan

L6 4 ANSWERS REGISTRY COPYRIGHT 2009 ACS on STN
IN 4,7,10,13-Tetraoxahexadecanedioic acid, 2,15-bis(methylene)-, 1,16-diethyl
ester, homopolymer
MF (C18 H30 O8)x
CI PMS

CM 1

PAGE 1-A



PAGE 1-B

—OEt

HOW MANY MORE ANSWERS DO YOU WISH TO SCAN? (1):0

=> file caplus

COST IN U.S. DOLLARS

SINCE FILE

TOTAL

ENTRY

SESSION

FULL ESTIMATED COST

380.40

380.62

FILE 'CAPLUS' ENTERED AT 13:47:25 ON 18 AUG 2009

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FILE COVERS 1907 - 18 Aug 2009 VOL 151 ISS 8

FILE LAST UPDATED: 17 Aug 2009 (20090817/ED)

REVISED CLASS FIELDS (/NCL) LAST RELOADED: Jun 2009

USPTO MANUAL OF CLASSIFICATIONS THESAURUS ISSUE DATE: Jun 2009

CAplus now includes complete International Patent Classification (IPC) reclassification data for the second quarter of 2009.

CAS Information Use Policies apply and are available at:

<http://www.cas.org/legal/infopolicy.html>

This file contains CAS Registry Numbers for easy and accurate substance identification.

The ALL, BIB, MAX, and STD display formats in the CA/CAplus family of databases have been updated to include new citing references information. This enhancement may impact record import into database management software. For additional information, refer to NEWS 9.

=> s 16

L7

3 L6

=> d ibib ti abs hitstr 16 1-3

YOU HAVE REQUESTED DATA FROM FILE 'REGISTRY' - CONTINUE? (Y)/N:n

=> d ibib ti abs hitstr 17 1-3

L7 ANSWER 1 OF 3 CAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2008:1012782 CAPLUS

DOCUMENT NUMBER: 149:269595

TITLE: Electron beam-curable composition and producing cured coating, ink or adhesive

INVENTOR(S): Kunita, Kazuto

PATENT ASSIGNEE(S): Fujifilm Corporation, Japan

SOURCE: U.S. Pat. Appl. Publ., 32pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|------|----------|-----------------|------------|
| US 20080200581 | A1 | 20080821 | US 2008-27648 | 20080207 |
| JP 2008201889 | A | 20080904 | JP 2007-39379 | 20070220 |
| PRIORITY APPLN. INFO.: | | | JP 2007-39379 | A 20070220 |

TI Electron beam-curable composition and producing cured coating, ink or adhesive

AB Producing an electron beam-cured coating includes forming on a substrate a layer of a curable composition that includes ≥ 1 compound $\text{CH}_2:\text{C}(\text{Q}_1)\text{CARbRaX}_1$ (I) and a step of curing the layer of the curable composition by irradiating with an electron beam. In I, Q_1 = cyano group or $-\text{COX}_2$ group, X_1 = H, organic residue, or polymer chain bonded to C atom CA via a heteroatom, or halogen, X_2 = H, organic residue, or polymer chain bonded to the carbonyl group via a heteroatom, or halogen, Ra and Rb = H, halogen, cyano group, or an organic residue, and X_1 and X_2 , Ra and Rb, and X_1 and Ra or Rb may be bonded to each other to form a cyclic structure. An example curable composition contained F 177 surfactant 0.03, cyclohexanone 20, and $\text{CH}_2:\text{C}(\text{COX}_2)\text{CH}_2\text{X}_1$ (X_2 = OEt; X_1 = $\text{OCH}_2\text{CH}_2\text{OCOMe}$) 10 parts.

IT 1047993-80-5P

RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)

(electron beam-curable composition with good adhesion to PET substrate)

RN 1047993-80-5 CAPLUS

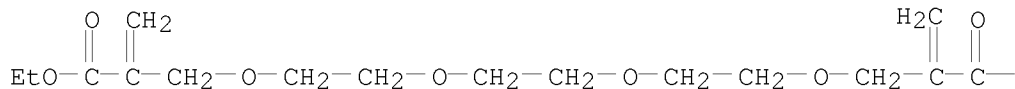
CN 4,7,10,13-Tetraoxahexadecanedioic acid, 2,15-bis(methylene)-, 1,16-diethyl ester, homopolymer (CA INDEX NAME)

CM 1

CRN 896113-18-1

CMF C18 H30 O8

PAGE 1-A



— OEt

L7 ANSWER 2 OF 3 CAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2006:673215 CAPLUS

DOCUMENT NUMBER: 145:113448

TITLE: Radiation-curable ink-jet inks containing
ethylenically polymerizable crosslinking agents with
excellent storage stability and sensitivity,
lithographic plates using them, and their manufacture

INVENTOR(S): Sugai, Shoji; Kunita, Kazuto

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 44 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|---------------|------|----------|-----------------|----------|
| JP 2006182990 | A | 20060713 | JP 2004-380665 | 20041228 |

PRIORITY APPLN. INFO.: JP 2004-380665 20041228

TI Radiation-curable ink-jet inks containing ethylenically polymerizable crosslinking agents with excellent storage stability and sensitivity, lithographic plates using them, and their manufacture

AB The inks contain polymerizable compds., colorants, and ≥ 1 crosslinking agents selected from those bearing 2 ethylenically polymerizable groups and those bearing ≥ 3 ethylenically polymerizable groups, thus giving wear-resistant hydrophobic images on hydrophilic supports without a development process.

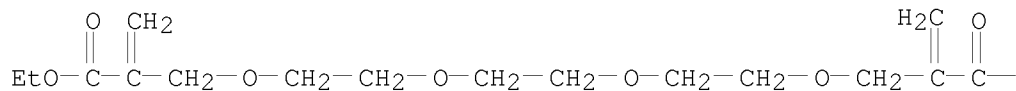
IT 896113-18-1

RL: TEM (Technical or engineered material use); USES (Uses)
(storage-stable radiation-curable ink-jet inks containing heteromethacrylic crosslinking agents for lithog. plates with good wear resistant)

RN 896113-18-1 CAPLUS

CN 4,7,10,13-Tetraoxahexadecanedioic acid, 2,15-bis(methylene)-, 1,16-diethyl ester (CA INDEX NAME)

PAGE 1-A



PAGE 1-B

— OEt

OS.CITING REF COUNT: 1 THERE ARE 1 CAPLUS RECORDS THAT CITE THIS RECORD
(1 CITINGS)

L7 ANSWER 3 OF 3 CAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2004:138005 CAPLUS

DOCUMENT NUMBER: 140:375551

TITLE: Synthesis and photopolymerizations of new hydroxyl-containing dimethacrylate crosslinkers

AUTHOR(S): Avci, Duygu; Mathias, Lon J.

CORPORATE SOURCE: Department of Chemistry, Bogazici University, Istanbul, 34342, Turk.

SOURCE: Polymer (2004), 45(6), 1763-1769

CODEN: POLMAG; ISSN: 0032-3861

PUBLISHER: Elsevier Science Ltd.

DOCUMENT TYPE: Journal

LANGUAGE: English

TI Synthesis and photopolymerizations of new hydroxyl-containing dimethacrylate crosslinkers

AB Two new hydroxyl-containing di(meth)acrylate monomers were synthesized from the reaction of Me α -chloromethylacrylate (MCMA) and of Et α -chloromethylacrylate (ECMA) with glycerol. The monomers were obtained as mixts. of two isomers in different ratios and in combination with the analogous trimethacrylate monomers. Each monomer was isolated by column chromatog. The photopolymn. of these isomer mixts. and the trimethacrylate monomers was investigated individually by photodifferential scanning calorimetry (photoDSC) at room temperature using 2,2'-dimethoxy-2-phenylacetophenone (DMPA) as a photoinitiator. The effect of hydrogen bonding on the rates of polymns. and conversions was examined. The results obtained for the synthesized monomers were compared to the values obtained for com. monomers. The hydroxyl-containing dimethacrylates polymerize much faster and to considerably higher conversion than the trimethacrylate monomers. The maximum rates of polymerization

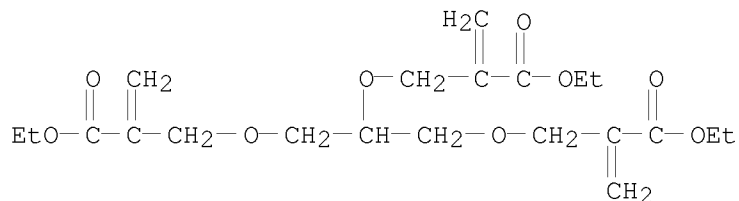
of the hydroxyl-containing monomers were higher than that of hexanediol dimethacrylate (HDDMA), comparable to glycerol dimethacrylate and lower than hexanediol diacrylate (HDDA) and 3-(acryloyloxy)-2-hydroxypropyl methacrylate (AHM).

IT 684213-81-8

RL: FMU (Formation, unclassified); FORM (Formation, nonpreparative) (in synthesis and photopolymn. of hydroxyl-containing dimethacrylate crosslinkers)

RN 684213-81-8 CAPLUS

CN 2-Propenoic acid, 2,2',2''-[1,2,3-propanetriyl]tris(oxymethylene)]tris-, triethyl ester (9CI) (CA INDEX NAME)



IT 684213-88-5P

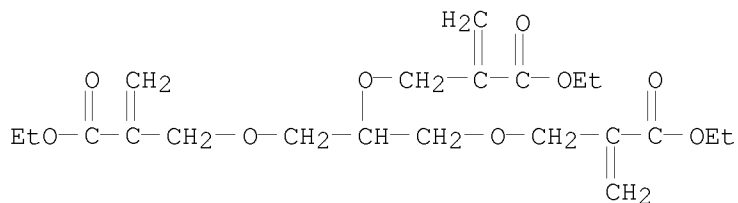
RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (synthesis and photopolymn. of hydroxyl-containing dimethacrylate crosslinkers)

RN 684213-88-5 CAPLUS

CN 2-Propenoic acid, 2,2',2''-[1,2,3-propanetriyl]tris(oxymethylene)]tris-, triethyl ester, homopolymer (9CI) (CA INDEX NAME)

CRN 684213-81-8

CMF C21 H32 09



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OS.CITING REF COUNT:      7      THERE ARE 7 CAPLUS RECORDS THAT CITE THIS RECORD
                                (7 CITINGS)
REFERENCE COUNT:          27      THERE ARE 27 CITED REFERENCES AVAILABLE FOR THIS
                                RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT
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COST IN U.S. DOLLARS

SINCE FILE

ENTRY

TOTAL

SESSION

FULL ESTIMATED COST

21.42

402.04

DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS)

SINCE FILE

TOTAL

ENTRY

SESSION

CA SUBSCRIBER PRICE

-2.46

-2.46

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DICTIONARY FILE UPDATES: 17 AUG 2009 HIGHEST RN 1174495-28-3

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REGISTRY includes numerically searchable data for experimental and predicted properties as well as tags indicating availability of experimental property data in the original document. For information on property searching in REGISTRY, refer to:

<http://www.cas.org/support/stngen/stndoc/properties.html>

 \Rightarrow

Uploading C:\Program Files\STNEXP\Queries\10567430clm58c.str

| | | |
|--|------------|---------|
| FULL ESTIMATED COST | 186.36 | 588.40 |
| DISCOUNT AMOUNTS (FOR QUALIFYING ACCOUNTS) | SINCE FILE | TOTAL |
| | ENTRY | SESSION |
| CA SUBSCRIBER PRICE | 0.00 | -2.46 |

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FILE COVERS 1907 - 18 Aug 2009 VOL 151 ISS 8
 FILE LAST UPDATED: 17 Aug 2009 (20090817/ED)
 REVISED CLASS FIELDS (/NCL) LAST RELOADED: Jun 2009
 USPTO MANUAL OF CLASSIFICATIONS THESAURUS ISSUE DATE: Jun 2009

CAplus now includes complete International Patent Classification (IPC) reclassification data for the second quarter of 2009.

CAS Information Use Policies apply and are available at:

<http://www.cas.org/legal/infopolicy.html>

This file contains CAS Registry Numbers for easy and accurate substance identification.

The ALL, BIB, MAX, and STD display formats in the CA/CAplus family of databases have been updated to include new citing references information. This enhancement may impact record import into database management software. For additional information, refer to NEWS 9.

=> s 19

L10 6 L9

=> d l10 ibib ti abs hitstr 1-6

L10 ANSWER 1 OF 6 CAPLUS COPYRIGHT 2009 ACS on STN
 ACCESSION NUMBER: 2008:1012782 CAPLUS
 DOCUMENT NUMBER: 149:269595
 TITLE: Electron beam-curable composition and producing cured coating, ink or adhesive
 INVENTOR(S): Kunita, Kazuto
 PATENT ASSIGNEE(S): Fujifilm Corporation, Japan
 SOURCE: U.S. Pat. Appl. Publ., 32pp.
 CODEN: USXXCO
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|----------------|------|----------|-----------------|----------|
| US 20080200581 | A1 | 20080821 | US 2008-27648 | 20080207 |
| JP 2008201889 | A | 20080904 | JP 2007-39379 | 20070220 |

PRIORITY APPLN. INFO.: JP 2007-39379 A 20070220

TI Electron beam-curable composition and producing cured coating, ink or adhesive

AB Producing an electron beam-cured coating includes forming on a substrate a layer of a curable composition that includes ≥ 1 compound $\text{CH}_2:\text{C}(\text{Q}_1)\text{CARbRaX}_1$ (I) and a step of curing the layer of the curable composition by irradiating with an electron beam. In I, Q_1 = cyano group or $-\text{COX}_2$ group, X_1 = H, organic residue, or polymer chain bonded to C atom CA via a heteroatom, or halogen, X_2 = H, organic residue, or polymer chain bonded to the carbonyl group via a heteroatom, or halogen, Ra and Rb = H, halogen, cyano group, or an organic residue, and X_1 and X_2 , Ra and Rb, and X_1 and Ra or Rb may be bonded to each other to form a cyclic structure. An example curable composition contained F 177 surfactant 0.03, cyclohexanone 20, and $\text{CH}_2:\text{C}(\text{COX}_2)\text{CH}_2\text{X}_1$ (X_2 = OEt; X_1 = $\text{OCH}_2\text{CH}_2\text{OCOMe}$) 10 parts.

IT 1047993-80-5P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (electron beam-curable composition with good adhesion to PET substrate)

RN 1047993-80-5 CAPLUS

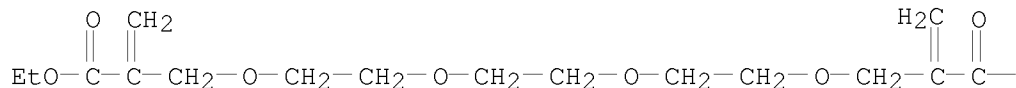
CN 4,7,10,13-Tetraoxahexadecanedioic acid, 2,15-bis(methylene)-, 1,16-diethyl ester, homopolymer (CA INDEX NAME)

CM 1

CRN 896113-18-1

CMF C18 H30 O8

PAGE 1-A



PAGE 1-B

— OEt

L10 ANSWER 2 OF 6 CAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2006:673215 CAPLUS

DOCUMENT NUMBER: 145:113448

TITLE: Radiation-curable ink-jet inks containing ethylenically polymerizable crosslinking agents with excellent storage stability and sensitivity, lithographic plates using them, and their manufacture

INVENTOR(S): Sugai, Shoji; Kunita, Kazuto

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 44 pp.
 CODEN: JKXXAF

DOCUMENT TYPE: Patent

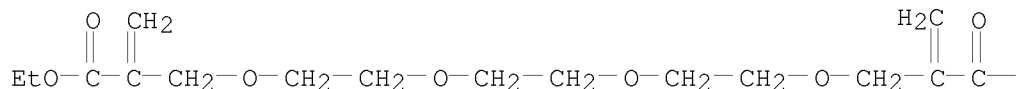
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

| | PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------------------|--|------|----------|-----------------|----------|
| | ----- | ---- | ----- | ----- | ----- |
| | JP 2006182990 | A | 20060713 | JP 2004-380665 | 20041228 |
| PRIORITY APPLN. INFO.: | | | | JP 2004-380665 | 20041228 |
| TI | Radiation-curable ink-jet inks containing ethylenically polymerizable crosslinking agents with excellent storage stability and sensitivity, lithographic plates using them, and their manufacture | | | | |
| AB | The inks contain polymerizable compds., colorants, and ≥ 1 crosslinking agents selected from those bearing 2 ethylenically polymerizable groups and those bearing ≥ 3 ethylenically polymerizable groups, thus giving wear-resistant hydrophobic images on hydrophilic supports without a development process. | | | | |
| IT | 896113-18-1 RL: TEM (Technical or engineered material use); USES (Uses) (storage-stable radiation-curable ink-jet inks containing heteromethacrylic crosslinking agents for lithog. plates with good wear resistant) | | | | |
| RN | 896113-18-1 CAPLUS | | | | |
| CN | 4,7,10,13-Tetraoxahexadecanedioic acid, 2,15-bis(methylene)-, 1,16-diethyl ester (CA INDEX NAME) | | | | |

PAGE 1-A



PAGE 1-B

—OEt

OS.CITING REF COUNT: 1 THERE ARE 1 CAPLUS RECORDS THAT CITE THIS RECORD
(1 CITINGS)

L10 ANSWER 3 OF 6 CAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2004:801227 CAPLUS

DOCUMENT NUMBER: 141:304331

TITLE: Photopolymerizable compositions with excellent laser sensitivity and storage stability and multifunctional crosslinker compounds for them

INVENTOR(S): Kunida, Kazuto

PATENT ASSIGNEE(S): Fuji Photo Film Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 94 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|--|------|----------|-----------------|----------|
| ----- | ---- | ----- | ----- | ----- |
| JP 2004269569 | A | 20040930 | JP 2003-58582 | 20030305 |
| JP 4070637 | B2 | 20080402 | | |
| EP 1466893 | A1 | 20041013 | EP 2004-5296 | 20040305 |
| R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC, PT, | | | | |

IE, SI, LT, LV, FI, RO, MK, CY, AL, TR, BG, CZ, EE, HU, PL, SK
 US 20050008967 A1 20050113 US 2004-793212 20040305
 US 7041711 B2 20060509

PRIORITY APPLN. INFO.: JP 2003-58582 A 20030305

TI Photopolymerizable compositions with excellent laser sensitivity and storage stability and multifunctional crosslinker compounds for them
 AB The compns. contain (CH₂:CZ1CO₂R1NHC₂O)mR₂(OCOCZ₂:CH₂)_n and (CH₂:CZ1CO₂R1NHC₂O)mR₂[CO₂CRaC(OCX₂):CH₂]_n [Z₁ = H, Me; Z₂ = H, Me, CHRbX₁; X_{1,2} = (un)substituted oxy, amino, or thio; Ra,b H, hydrocarbyl; R₁ = (O-containing) aliphatic hydrocarbon group; R₂ = (O-containing) aliphatic hydrocarbon group; m, n = 1-5] and preferably alkali-soluble polyurethanes, thus giving lithog. plates for direct platemaking by laser exposure with good wear resistance.

IT 765292-19-1P 765292-21-5P
 RL: IMF (Industrial manufacture); TEM (Technical or engineered material use); PREP (Preparation); USES (Uses)
 (photopolymerizable compns. with good laser sensitivity and storage stability for lithog. plates with good wear resistance)

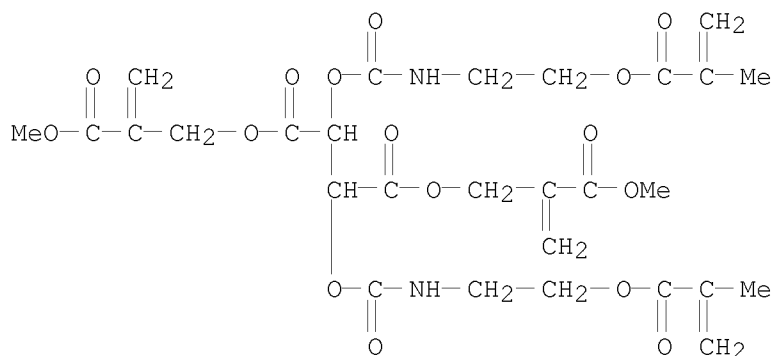
RN 765292-19-1 CAPLUS

CN Butanedioic acid, 2,3-bis[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]oxy]-, bis[2-(methoxycarbonyl)-2-propenyl] ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 765292-18-0

CMF C28 H36 N2 O16



RN 765292-21-5 CAPLUS

CN Butanedioic acid, [[[[2-[(2-methyl-1-oxo-2-propenyl)oxy]ethyl]amino]carbonyl]oxy]-, bis[2-(methoxycarbonyl)-2-propenyl] ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 765292-20-4

CMF C21 H27 N O12



ACCESSION NUMBER: 2004:138005 CAPLUS

DOCUMENT NUMBER: 140:375551

TITLE: Synthesis and photopolymerizations of new
hydroxyl-containing dimethacrylate crosslinkers

AUTHOR(S) : Avci, Duygu; Mathias, Lon J.

CORPORATE SOURCE: Department of Chemistry, Bogazici University,
Istanbul, 34342, Turk.

SOURCE: Polymer (2004), 45(6), 1763-1769

CODEN: POLMAG; ISSN: 0032-3861

PUBLISHER: Elsevier Science Ltd.

DOCUMENT TYPE: Journal

LANGUAGE: English

TI Synthesis and photopolymerizations of new hydroxyl-containing dimethacrylate crosslinkers

AB Two new hydroxyl-containing di(meth)acrylate monomers were synthesized from the reaction of Me α -chloromethylacrylate (MCMA) and of Et α -chloromethylacrylate (ECMA) with glycerol. The monomers were obtained as mixts. of two isomers in different ratios and in combination with the analogous trimethacrylate monomers. Each monomer was isolated by column chromatog. The photopolymn. of these isomer mixts. and the trimethacrylate monomers was investigated individually by photodifferential scanning calorimetry (photoDSC) at room temperature using 2,2'-dimethoxy-2-phenylacetophenone (DMPA) as a photoinitiator. The effect of hydrogen bonding on the rates of polymns. and conversions was examined. The results obtained for the synthesized monomers were compared to the values obtained for com. monomers. The hydroxyl-containing dimethacrylates polymerize much faster and to considerably higher conversion than the trimethacrylate monomers. The maximum rates of polymerization

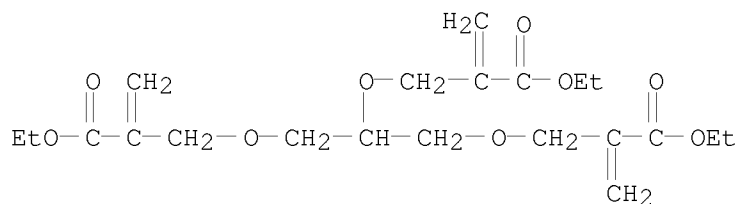
of the hydroxyl-containing monomers were higher than that of hexanediol dimethacrylate (HDDMA), comparable to glycerol dimethacrylate and lower than hexanediol diacrylate (HDDA) and 3-(acryloyloxy)-2-hydroxypropyl methacrylate (AHM).

IT 684213-81-8 684213-82-9

RL: FMU (Formation, unclassified); FORM (Formation, nonpreparative)
(in synthesis and photopolymn. of hydroxyl-containing dimethacrylate
crosslinkers)

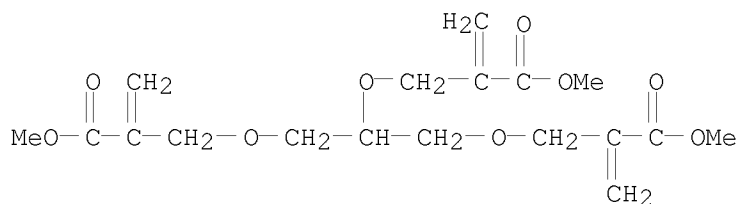
RN 684213-81-8 CAPLUS

CN 2-Propenoic acid, 2,2',2''-[(1,2,3-propanetriyl)tris(oxymethylene)]tris-, triethyl ester (9CI) (CA INDEX NAME)



RN 684213-82-9 CAPLUS

CN 2-Propenoic acid, 2,2',2''-[1,2,3-propanetriyltris(oxymethylene)]tris-, trimethyl ester (9CI) (CA INDEX NAME)



IT 684213-87-4P 684213-88-5P

RL: PRP (Properties); SPN (Synthetic preparation); PREP (Preparation) (synthesis and photopolymn. of hydroxyl-containing dimethacrylate crosslinkers)

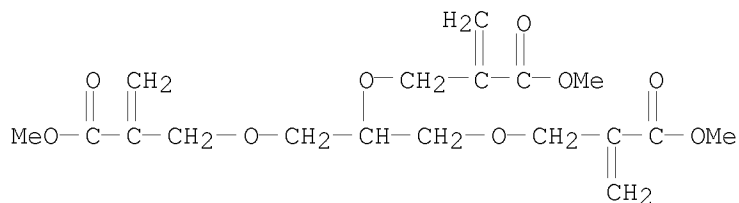
RN 684213-87-4 CAPLUS

CN 2-Propenoic acid, 2,2',2''-[1,2,3-propanetriyltris(oxymethylene)]tris-, trimethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 684213-82-9

CMF C18 H26 O9



RN 684213-88-5 CAPLUS

CN 2-Propenoic acid, 2,2',2''-[1,2,3-propanetriyltris(oxymethylene)]tris-, triethyl ester, homopolymer (9CI) (CA INDEX NAME)

CM 1

CRN 684213-81-8

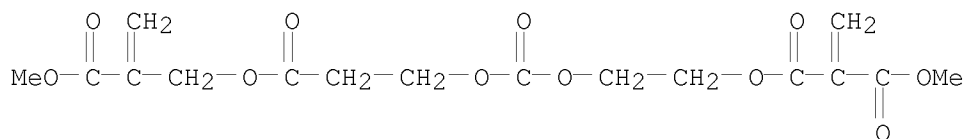
CMF C21 H32 O9

TI Plate-making method of printing plate
AB A plate-making method of a printing plate comprises exposing a printing plate precursor having a photosensitive layer comprising a photopolymerizable composition containing (1) a crosslinking agent having two ethylenic polymerizable groups and (2) a crosslinking agent having three or more ethylenic polymerizable groups, and development processing the exposed printing plate precursor with an alkali developer having a pH of ≤ 12.5 .
IT 500769-95-9
RL: POF (Polymer in formulation); TEM (Technical or engineered material use); USES (Uses)
(photopolymerizable composition for plate-making method of printing plate containing)
RN 500769-95-9 CAPLUS
CN 4,7,9,13-Tetraoxahexadecanedioic acid, 2,15-bis(methylene)-3,8,12-trioxo-, dimethyl ester, polymer with 2-[[[3-[(1-oxo-2-propenyl)oxy]-2,2-bis[[[(1-oxo-2-propenyl)oxy]methyl]propoxy]methyl]-2-[[[(1-oxo-2-propenyl)oxy]methyl]-1,3-propanediyl di-2-propenoate (9CI) (CA INDEX NAME)
CM 1
CRN 500769-94-8

CM 2

CRN 29570-58-9

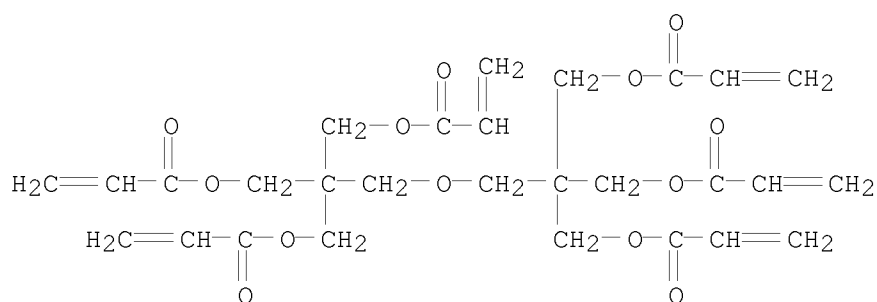
CMF C28 H34 O13



CM 2

CRN 29570-58-9

CMF C28 H34 O13



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(5 CITINGS)

REFERENCE COUNT: 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS
RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L10 ANSWER 6 OF 6 CAPLUS COPYRIGHT 2009 ACS on STN

ACCESSION NUMBER: 2000:484355 CAPLUS

DOCUMENT NUMBER: 133:112451

TITLE: Heat development photosensitive material for printing
platemaking

INVENTOR(S): Muramatsu, Yasuhiko

PATENT ASSIGNEE(S): Konica Co., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 47 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

| PATENT NO. | KIND | DATE | APPLICATION NO. | DATE |
|------------|------|------|-----------------|------|
|------------|------|------|-----------------|------|

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|---------------|---|----------|--------------|----------|
| JP 2000199936 | A | 20000718 | JP 1999-1159 | 19990106 |
|---------------|---|----------|--------------|----------|

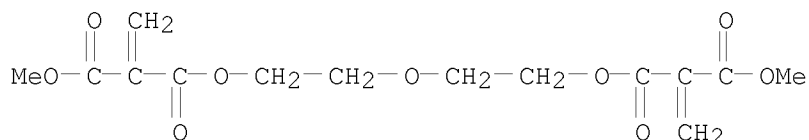
PRIORITY APPLN. INFO.: JP 1999-1159 19990106

TI Heat development photosensitive material for printing platemaking

AB The title photosensitive material contains, on a support, an organic Ag salt, photosensitive Ag halide grains, a reducing agent, and either (1) a compound having ≥ 2 cyclic acid anhydride groups, (2) a compound having ≥ 2 acetal groups, or (3) a compound having ≥ 2 2-substituted acrylate groups or (4) ≥ 1 carbodiimide compound and ≥ 1 acid anhydride. The material shows improved film strength and storage stability and high contrast even upon storage for a long time.

IT 283595-16-4

RL: DEV (Device component use); MOA (Modifier or additive use); TEM
 (Technical or engineered material use); USES (Uses)
 (photothermog. material containing acid anhydride, acetal compound,
 acrylate,
 or carbodiimide)
 RN 283595-16-4 CAPLUS
 CN Propanedioic acid, methylene-, oxydi-2,1-ethanediyl dimethyl ester (9CI)
 (CA INDEX NAME)



OS.CITING REF COUNT: 1 THERE ARE 1 CAPLUS RECORDS THAT CITE THIS RECORD
 (2 CITINGS)

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 DICTIONARY FILE UPDATES: 17 AUG 2009 HIGHEST RN 1174495-28-3

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=> S 896113-18-1/RN

L11 1 896113-18-1/RN

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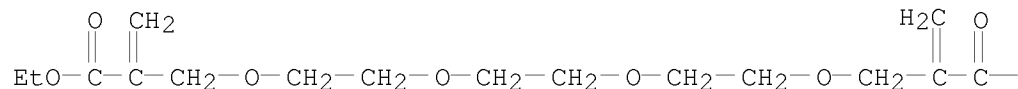
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L11 ANSWER 1 OF 1 REGISTRY COPYRIGHT 2009 ACS on STN
RN 896113-18-1 REGISTRY
CN 4,7,10,13-Tetraoxahexadecanedioic acid, 2,15-bis(methylene)-, 1,16-diethyl
ester (CA INDEX NAME)
OTHER CA INDEX NAMES:
CN 4,7,10,13-Tetraoxahexadecanedioic acid, 2,15-bis(methylene)-, diethyl
ester (9CI)
MF C18 H30 O8
CI COM
SR CA
LC STN Files: CA, CAPLUS
DT.CA CAplus document type: Patent
RL.P Roles from patents: USES (Uses)

PAGE 1-A



PAGE 1-B

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PROPERTY DATA AVAILABLE IN THE 'PROP' FORMAT

1 REFERENCES IN FILE CA (1907 TO DATE)
1 REFERENCES IN FILE CAPLUS (1907 TO DATE)

=> SET NOTICE LOGIN DISPLAY

NOTICE SET TO OFF FOR DISPLAY COMMAND
SET COMMAND COMPLETED

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=> log off
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LOGOFF? (Y)/N/HOLD:y
STN INTERNATIONAL LOGOFF AT 14:16:20 ON 18 AUG 2009